FORM PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY.DOCKET NO. 06381P USA

APPLICANT

SERIAL NO.

10/624357

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Aaron Scott Lukas, et al.

(37 CFR 1.98(b))

FILING DATE 7/21/03

GROUP

2813

12.00
2001 2002 2002 2003 2003 2003

_	EXAM- INER INITIAL				DOCU	MENT	NUMBE	R		DATE	NAME	CLASS	SUBCLASS	FILING DATE
	113		4	6	0	3	1	6	8	7/29/1986	S. Sasaki, et al.	522	18	2/19/1985
	B_		5_	6	0	9	9	2	5	3/11/1997	R. C. Camilletti, et al.	427	503	12/4/1995
	113	<u> </u>	5_	9	7	0	3	8	4	10/19/1999	S. Yamazaki, et al.	438	795	8/2/1995
Ί	भ		6_	0	1	7	8	0	6	1/25/2000	K. C. Harvey	438	475	7/28/1998
1	<u>) R</u>		6	0	4	2	9	9	4	3/28/2000	J. Yang, et al.	430	296	1/8/1999
	113		6	1	6	8	9	8	0	1/2/2001	S. Yamazaki, et al.	438	162	9/26/1996
1)B		6	2	8	4	0	5	0	9/4/2001	J. Shi, et al.	118	715	5/18/1998
1	JR	-81-	0	0	3	8	9	1	9	11/8/2001	I. L. Berry, III, et al.	428	446	3/19/2001
1	<u> </u>	02	0	1	0	2	4	L_1	3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
	<u> </u>	_02_	0	1	0	6	5	0	0	8/8/2002	R. Albano, et al.	428	304.4	9/14/2001
)B	-02-	0	1	4	2	5	8	5	10/3/2002	R. P. Mandal	438	633	3/4/2002
C	JR	-03	0	0	3	2	3	0	0	2/13/2003	C. Waldfried, et al.	438	725	5/14/2001
1	YS.	03-	0	0	5	4	1	1	5	3/20/2003	R.Albano, et al.	427	487	9/14/2001

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

			DOCUMENT NUMBER						DATE COUNTRY	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
		İ								ľ	1	1	YES	NO
(AR)	WO	9	7	0	0	5	3_	5		World			X	
$\Box B \Box$	WO	02	9	6	5	5	3	4		World			Х	
		<u> </u>	L	<u></u>										
				1	L		1							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

NB	E. G. Parada, et al., "Improvement of Silicon Oxide Film Properties by Ultraviolet Excimer Lamp Annealing," Applied Surface Science 86, pp. 294-298 (1995).
UB	A. Guo, et al., "Highly Active Visible-Light Photocatalysts for Curing a Ceramic Precursor1," Chem Mater. 10, pp. 531-536 (1998).
NB	T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films," Chem. Mater. 12, pp. 3879-3884 (2000).
NB	M. Brinkmann, et al., *Room-Temperature Synthesis of a-SiO ₂ Thin Films by UV-Assisted Ozonolysis of a Polymer Precursor, *Chem. Mater. 13, pp. 967-972 (2001).
nB	A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light," Chem. Mater. 12, pp. 3842-3847 (2000).
UB	M. Ouyang, et al., *Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes,* Chem. Mater. 12, pp. 1591-1596 (2000).
an an	Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
NB	C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER		/
COVINITED	1\/	4
	Nema	there znv
	11010	

DATE CONSIDERED 11-30-04

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Includ copy of this form with next communication to applicant.

PTO/SB/08A (08-03)
Approved for use through 07/31/2008. OMB 0651-0031
U.S. Patent and Tradamark Office; U.S. DEPARTMENT OF COMMERCE
to a collection of information unless it contains a valid OMB control number.

Sub	stitute for form 14	49/PTO		Complete if Known			
				Application Number	10/624,357		
INFO	RMATION	DISCLO	SURE	Filing Date	July 21, 2003		
STAT	TEMENT E	BY APPL	ICANT	First Named Inventor	Aaron Scott Lukas, et al.		
(Use as many she	ets as nacess	ery)	Art Unit	2813		
				Examiner Name	Berezny, Nema O.		
Sheet	1	of	1	Attorney Docket Number	06381P USA		
				I	I		

			U. S. PATENT DO	DCUMENTS		
Examiner nitlels*	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, When Relevant Passages or	
		Number-Kind Code ^{2 (3 knows)}			Relevant Figures Appear	
15-		^{US-} 5,935,646	08-10-1999	Raman, et al.		
		^{US-} 6,231,989	05-15-2001	Chung, et al.		
		^{US-} 6,426,236	07-30-2020	Ishizaka,et al.	7/2002	
		^{US-} 6,472,076	10-29-2002	Hacker		
		^{US-} 2002/0132496	09-19-2002	Bail, et al.		
		^{US-} 2003/0003288	01-02-2003	Nakata, et al.		
		US- 2003/0087042	05-08-2003	Murakami, et al.		
		us- 2003/0162034	08-28-2003	O'Neill, et al.		
		^{US-} 2003/0198742	10-23-2003	Vrtis, et al.		
		US- 2003/0232137	12-18-2003	Vrtis, et al.		
$T^{}$		^{US-} 2004/0096593	05-20-2004	Lukas, et al.		
V		us 2004/0096672	05-20-2004	Lukas, et al.		
		US-				
		US-				
		U\$-				
		US-		V		

	-	FOREI	GN PATENT D	OCUMENTS		· · · · · · · · · · · · · · · · · · ·
Examiner Initials*	Cite No.1	Foreign Patent Oocument	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages.or	
		Country Code ³ Number ⁴ Kind Code ⁵ (7			Relevant Eigures Appear	Τ ⁶

Examiner	08	Date	11 4/6/0
Signature		Considered	17 4106

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformation and not considered. Include copy of this form with next communication to applicant. 'Applicant's unique citation designation number (optional). 'See Kinds Codes of USPTO Patent Documents at www.uspio.gov or MPEP 901.04. 'Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). "For Japanese patent documents, the Indication of the year of the reign of the Emperor must precede the serial number of the patent document. 'Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 it possible. 'Applicant is to place a check mark here if English language Translation is attached.

This collection of Information is required by 37 CFR 1.97 and 1.88. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.